(19) World Intellectual Property Organization

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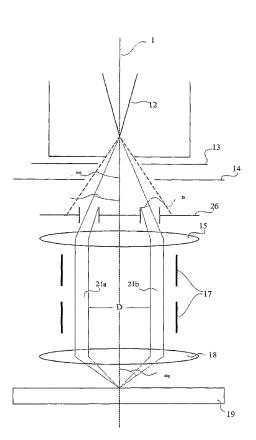
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- (71) Applicant (for all designated States except US): ICT, INTEGRATED CIRCUIT TESTING GESELLSCHAFT FÜR HALBLEITERPRÜFTECHNIK mbH [DE/DE]; Ammerthalstr. 20a, 85551 Heimstetten (DE).
- (72) Inventor; and
- (75) Inventor/Applicant (for US only): FROSIEN, Jürgen [DE/DE]; Kufsteinerstrasse 16a, 85521 Riemerling (DE).

- (74) Agents: ZIMMERMANN, Gerd et al.; Zimmermann & Partner, P.O. Box 330 920, 80069 Munich (DE).
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[Continued on next page]

(54) Title: HIGH CURRENT DENSITY PARTICLE BEAM SYSTEM



(57) Abstract: The present invention relates to charged particle beam devices. The devices comprise an emitter (12) for emitting charged particles; an aperture arrangement (26; 86) with at least two apertures (36) for separating the emitted charged particles into at least two independent charged particle beams; and an objective lens (18) for focusing the at least two independent charged particle beams, whereby the independent charged particle beams are focused onto the same location within the focal plane.

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SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

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